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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/825,648	04/04/2001	Joseph Wytman	003481.P009D	9902
8791	7590 11/17/2003		EXAMINER	
BLAKELY SOKOLOFF TAYLOR & ZAFMAN			MUTSCHLER, BRIAN L	
12400 WILSHIRE BOULEVARD, SEVENTH FLOOR LOS ANGELES, CA 90025			ART UNIT	PAPER NUMBER
	., .		1753	
	•		DATE MAIL ED. 11/17/2002	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)
Examiner-Initiated Interview Summary	09/825,648	WYTMAN, JOSEPH
	Examiner	Art Unit
	Brian L. Mutschler	1753
All Participants:	Status of Application: After	er Final Rejection Mailed
(1) Brian L. Mutschler.	(3)	
(2) <u>Larry Johnson</u> .	(4)	
Date of Interview: 13 November 2003	Time: <u>1:30pm</u>	
Type of Interview: ☐ Telephonic ☐ Video Conference ☐ Personal (Copy given to: ☐ Applicant ☐ Applicant Exhibit Shown or Demonstrated: ☐ Yes ☐ No If Yes, provide a brief description:	nt's representative)	
Part I.		
Rejection(s) discussed: all		
Claims discussed: all pending		
Prior art documents discussed: Getchel (U.S. Pat. No. 6,019,164)		
Part II.	•	
SUBSTANCE OF INTERVIEW DESCRIBING THE GENER See Continuation Sheet	RAL NATURE OF WHAT WAS	DISCUSSED:
Part III.	·	
 It is not necessary for applicant to provide a separate redirectly resulted in the allowance of the application. The of the interview in the Notice of Allowability. It is not necessary for applicant to provide a separate redid not result in resolution of all issues. A brief summary 	examiner will provide a writte ecord of the substance of the	en summary of the substance interview, since the interview
		•
The 1 Motolle Windows		
7 Juan 1 Mitable 11/13/2003 (Applicant)	Applicant's Representative Sign	anature – if appropriate)

Continuation of Substance of Interview including description of the general nature of what was discussed: Mr. Johnson raised a question about the Getchel reference and its use in the rejection of the claims. Specifically, the use of the chuck in Getchel as a "non-tilting" chuck in one embodiment (see col. 6, line 38+) was discussed in regard to the "tilting" limitation in claim 17. While Getchel does suggest that at least one embodiment is non-tilting, it appears that the embodiment shown in Figure 5 and described beginning in column 12 at line 36 is capable of tilting by the use of springs (206) holding the upper and lower supports together. However, it was suggested that changing the "tilting" limitation in claim 17 to positively recite a step of "preventing or reducing leakage of the processing fluid by tilting the wafer to compliantly engage the wafer and the sleeve" would distinguish the instant claim over the teachings of Getchel. The chuck in Getchel is designed to compensate for thermal expansion, and Getchel does not disclose tilting the chuck to prevent leakage or to compliantly engage the wafer to the sleeve. The interview clarified the positions regarding the claims with respect to the Getchel reference, but no agreement was reached..